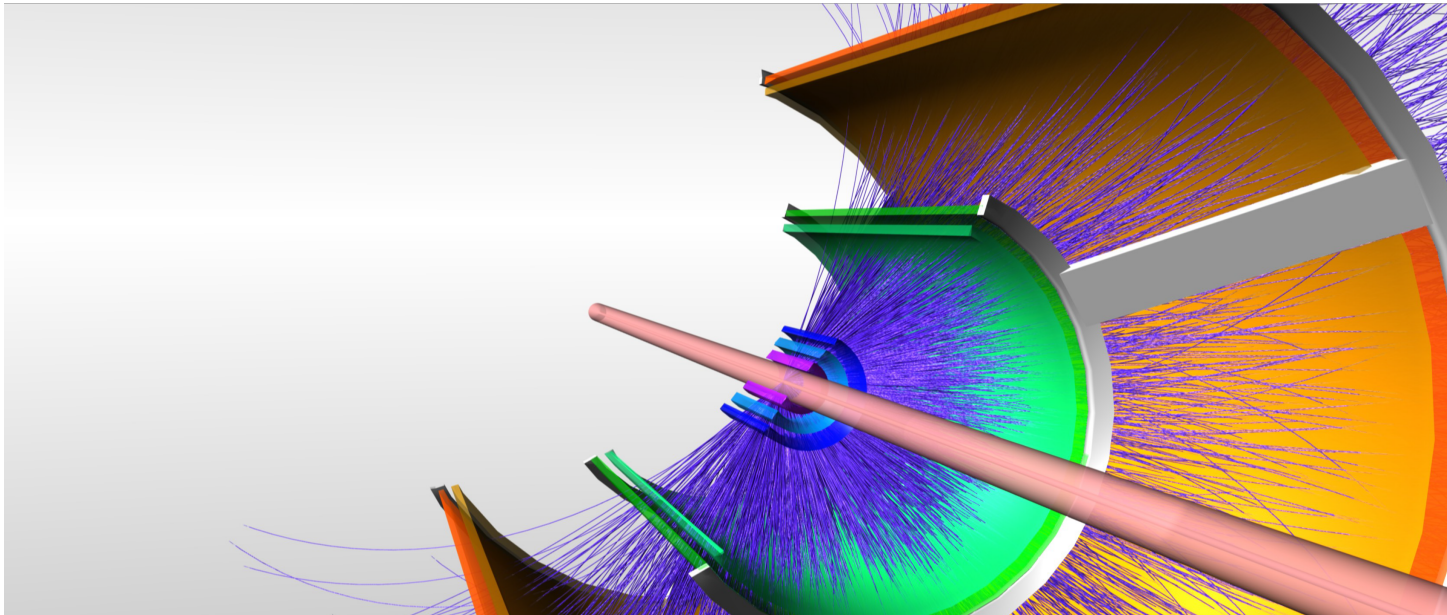


The upgrade of the ALICE Inner Tracking System

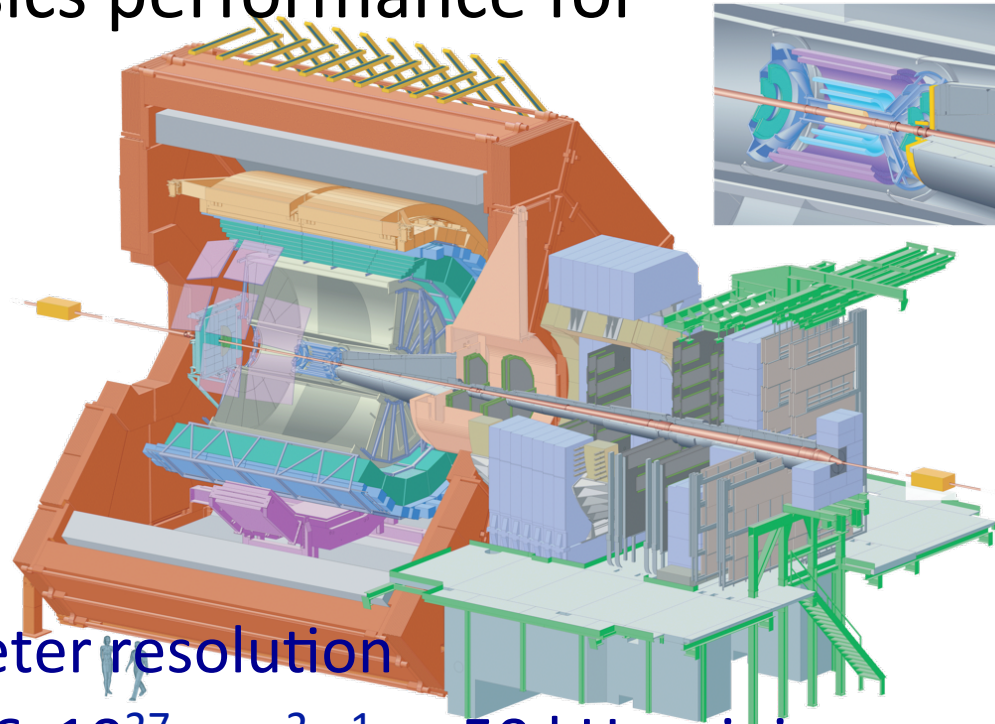


S.Beolè
Università di Torino & INFN
on behalf of the ALICE
Collaboration

11th International Conference on Large Scale
Applications and Radiation Hardness of
Semiconductor Detectors 3-5 July, Florence, Italy

Motivations for the ALICE upgrade

- **Why:** improve the physics performance for
 - Heavy flavor at low p_T
 - Quarkonia
 - Low-mass di-leptons
 - Heavy nuclear states
- **How:**
 - Improve impact parameter resolution
 - Higher LHC luminosity: $6 \times 10^{27} \text{ cm}^{-2} \text{ s}^{-1}$ -> 50 kHz minimum bias Pb-Pb interactions
- **What:**
 - New beampipe, TPC and ITS, all readout electronics, etc...

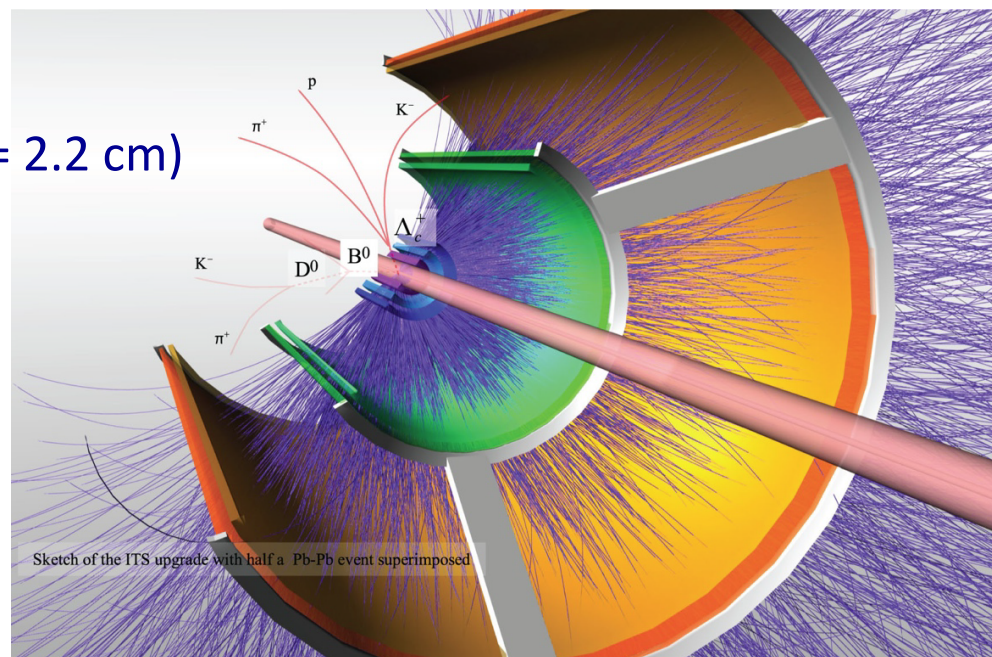


ITS Upgrade features



- Good spatial resolution: improve secondary vertex resolution by factor ≈ 3 (5) in $r\phi$ (z):

- smaller beam pipe ($R = 1.9$ cm)
- inner layer as close as possible ($R = 2.2$ cm)
- more layers
- less material budget
 - thin sensors (goal: $0.3-8\%$ X_0 /layer)
 - thinner beam pipe ($\Delta R = 800\mu\text{m}$)
- smaller pixel size:
 - monolithic pixels ($20\mu\text{m} \times 20\mu\text{m}$)

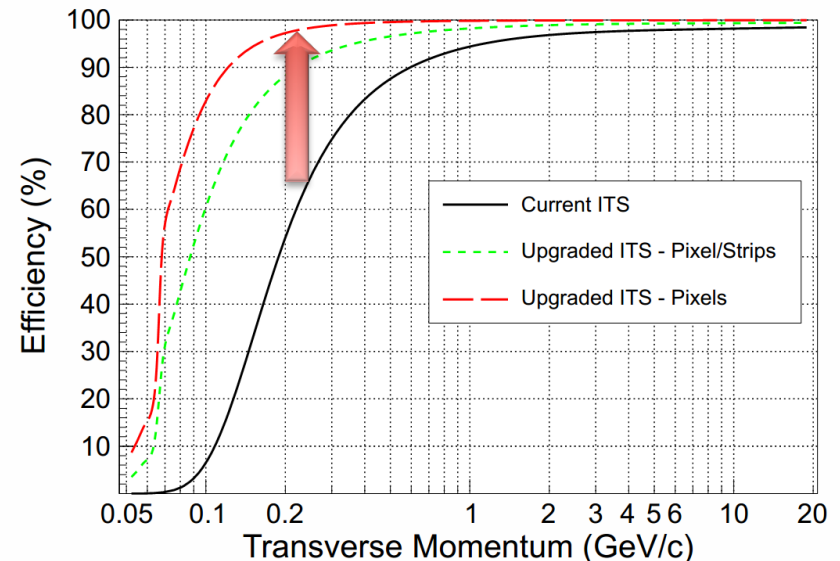
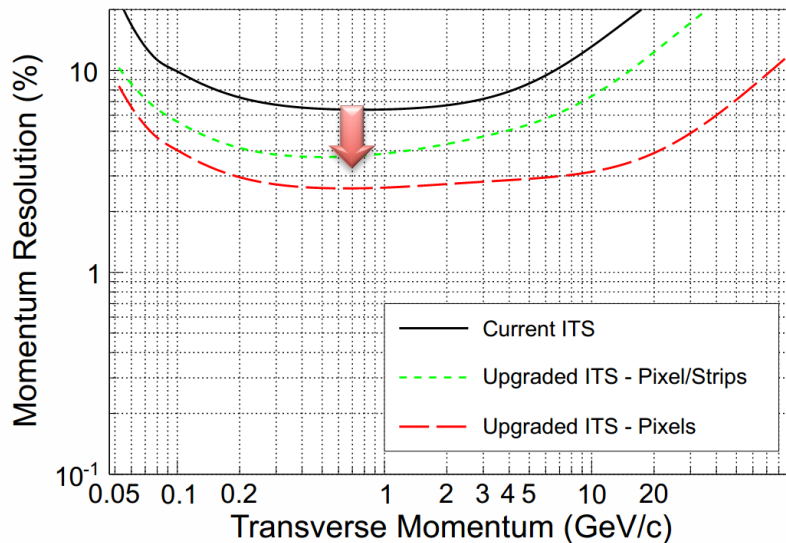
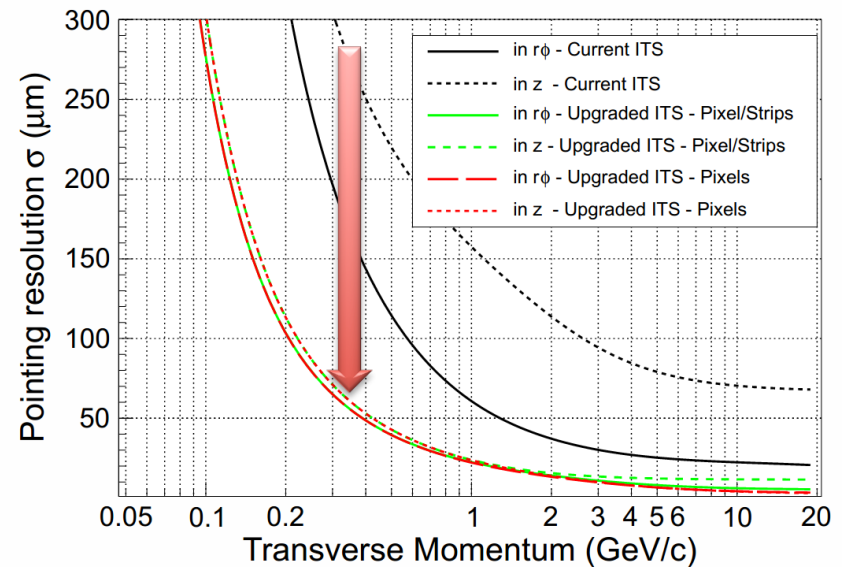


- Radiation level:
 - 700 kRad + 10^{13} $n_{\text{eq}}/\text{cm}^2$ for the full integrated luminosity (innermost layer including a safety factor = 4)
- high standalone efficiency and p_T resolution
- fast readout:
 - 500 Hz \rightarrow 50 kHz in Pb-Pb
 - ~ 200 kHz in pp
- fast removal/insertion to ease possible yearly maintenance

Expected improvements of the detector performance:



- 3 x better pointing resolution
- 2 x better standalone tracking efficiency at low p_T
- 2.5 x better standalone momentum resolution



Conceptual detector layout:



Layer	Type	R [cm]	$\pm z$ [cm]	Intrinsic resolution [μm]		Material budget [% X_0]
				$r\phi$	z	
	Beam pipe	2.0	-	-	-	0.22
0		2.2	11.2	4	4	0.3
1	Pixel	2.8	12.1	4	4	0.3
2		3.6	13.4	4	4	0.3
3		20.0	39.0	4	4	0.8
4		22.0	41.8	4	4	0.8
5	Pixel	41.0	71.2	4	4	0.8
6		43.0	74.3	4	4	0.8



ALICE

Inner barrel

Inner Barrel (IB): 3 layers pixels

Radial position (mm): 22,28,36

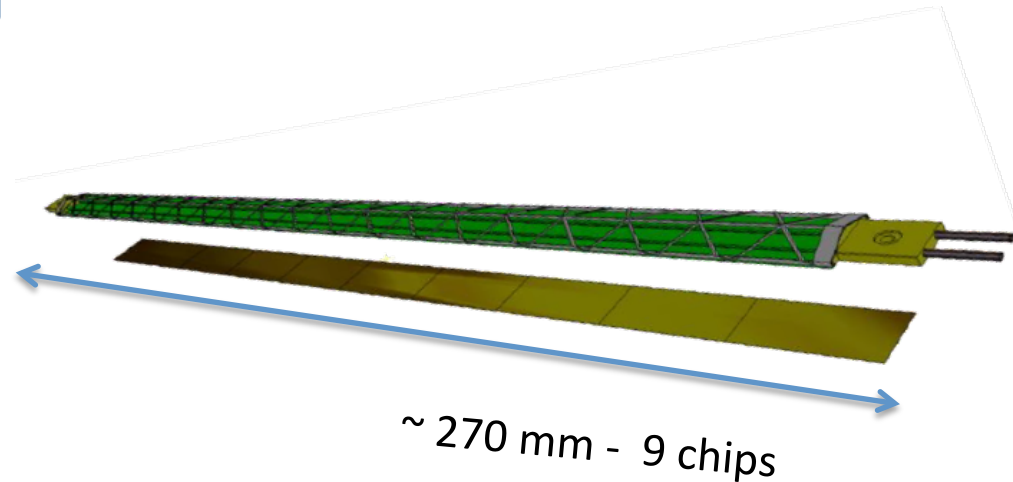
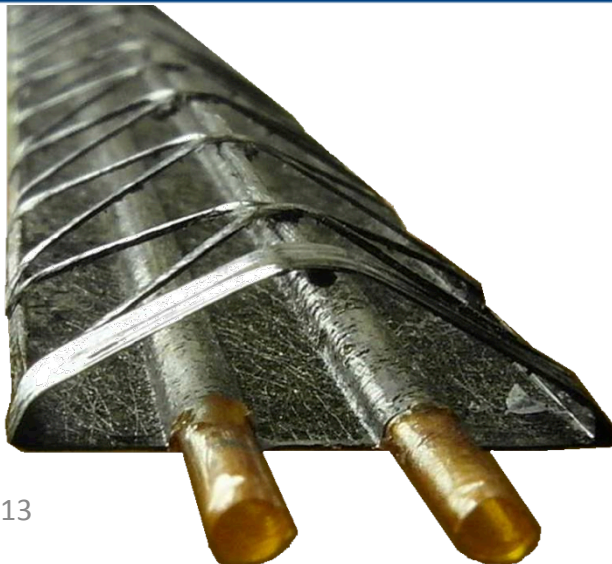
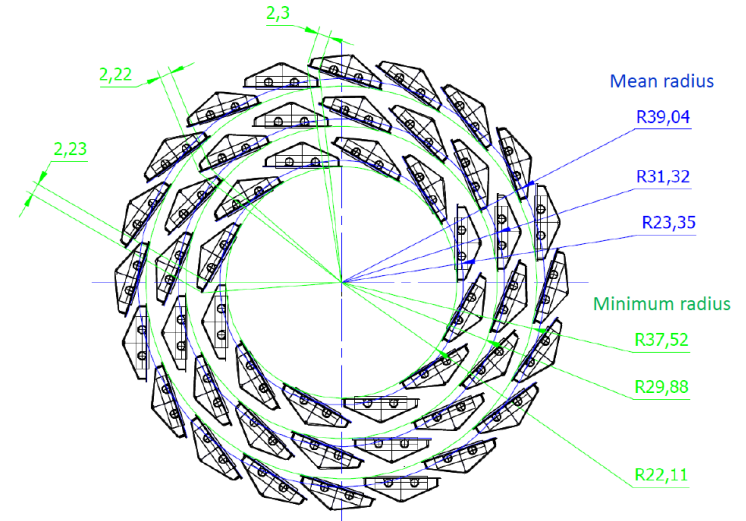
Length in z (mm): 270

Nr. of staves: $12 + 16 + 20 = 48$

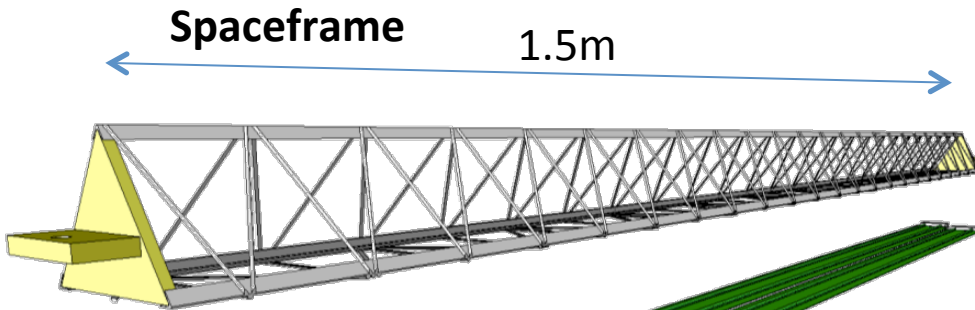
Nr. of chips/stave: 9

Pixel size: $\sim 20 \mu\text{m} \times 20 (30) \mu\text{m}$

Material thickness: $\sim 0.3\% X_0$



Outer barrel



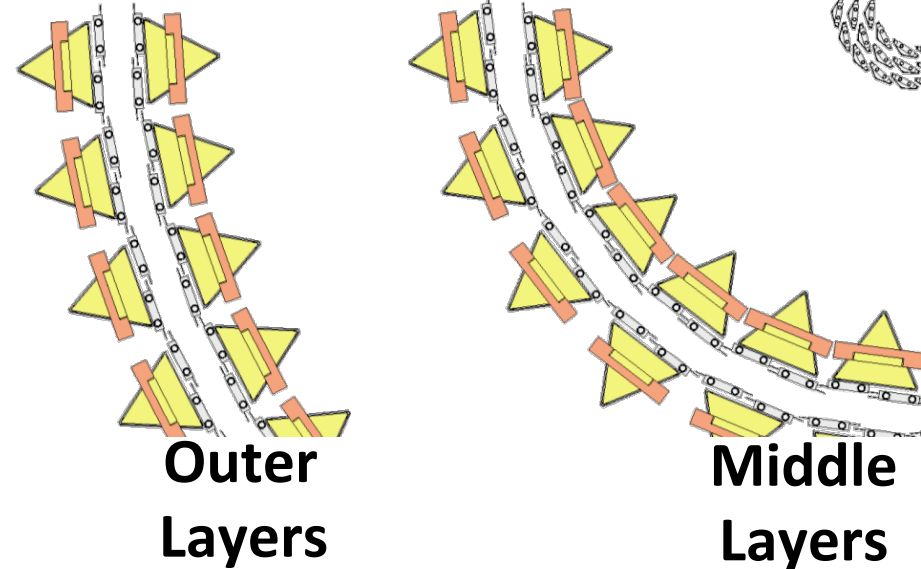
Cold Plate

Cold Plate

Stave

Module

Each module consists of a hybrid integrated circuit, i.e. a number of pixel chips (e.g. $2 \times N$) bonded on a flexible printed circuit, which might be glued on a carbon ply



Outer Layers

Middle Layers

Half-Stave

Each half-stave will consist of a number of modules glued on a common cold plate

Outer Barrel (OB): 4 layers pixels

Radial position (mm): 200, 220, 410, 430

Length in z (mm): 843, 1475

Nr. of staves: 48, 52, 96, 102

Nr. of chips/stave: 56, 56, 98, 98

Nr. of chips/layer: 2688, 2912, 9408, 9996

Material thickness: $\sim 0.8\% X_0$



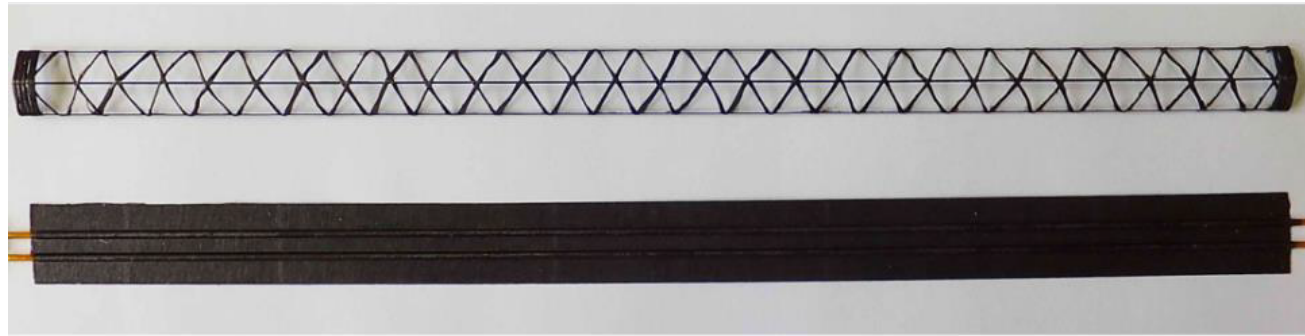
Space frame & cooling

- Inner barrel:
 - Embedded kapton pipes
 - Polyimide microchannels
 - Silicon microchannel
- Outer barrel:
 - Embedded kapton pipes



Wound Truss Structure plus Carbon Plate with Embedded Pipes

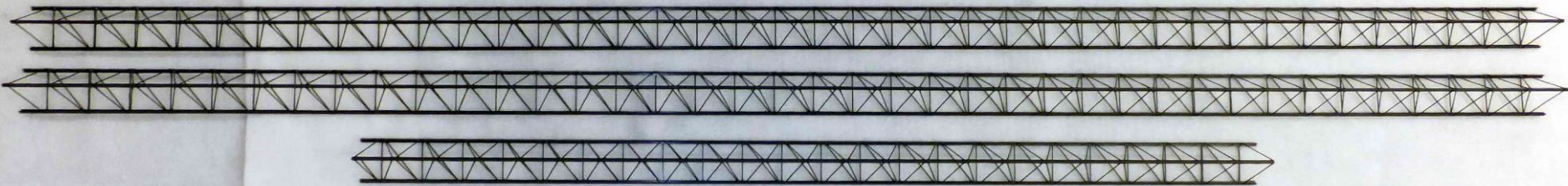
Inner barrel stave



<i>Weight</i>	1.8 grams
<i>X/X0</i>	0.31%
<i>Cooling capacity</i>	<25°C at 0.3W/cm ²
	<30°C at 0.5W/cm ²

Outer barrel stave

LAYER 5,6 length 1526mm. Weight 33,6g



LAYER 3,4 length 900mm. Weight 18g

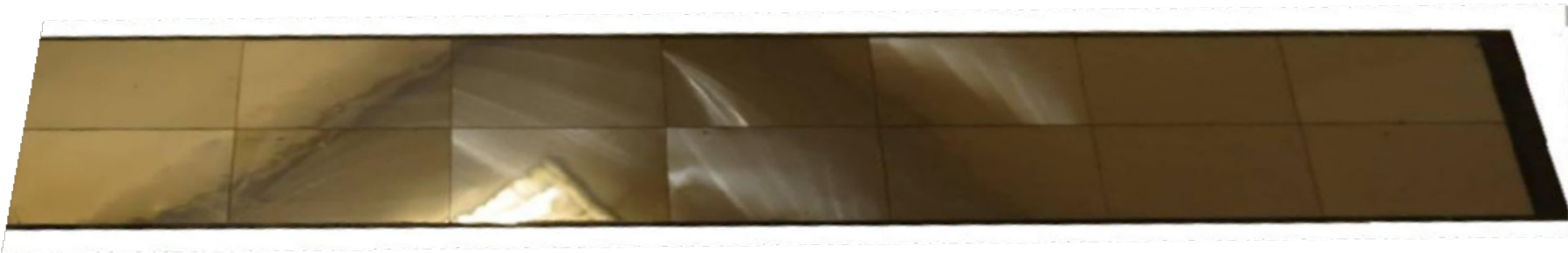
Outer barrel stave and module

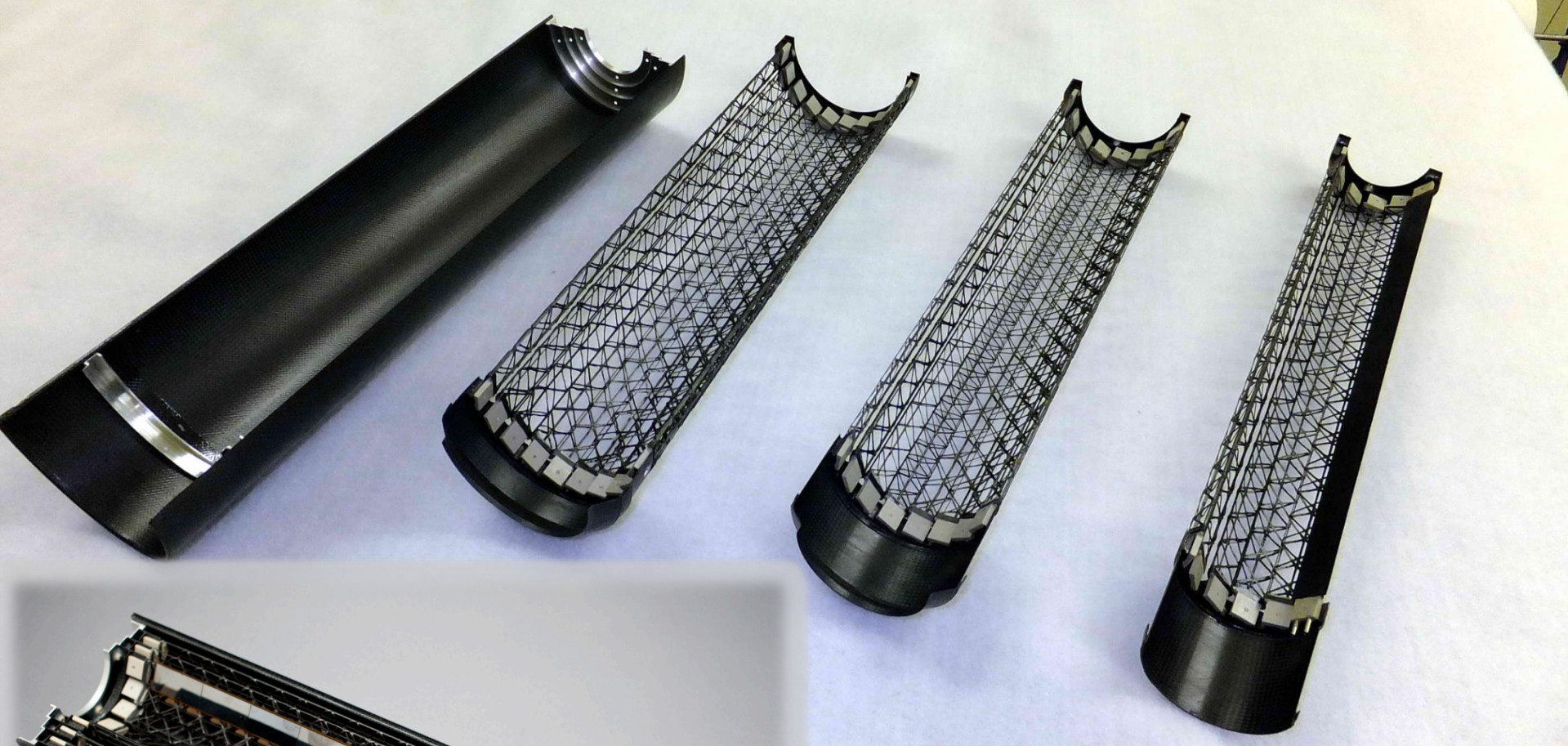
Overall material budget per layer X/X_0 : $\sim 0.8\%$



Design in progress

- Module: $2 \times N$ pixel chips
- FPC
- Cooling
- Assembly procedure





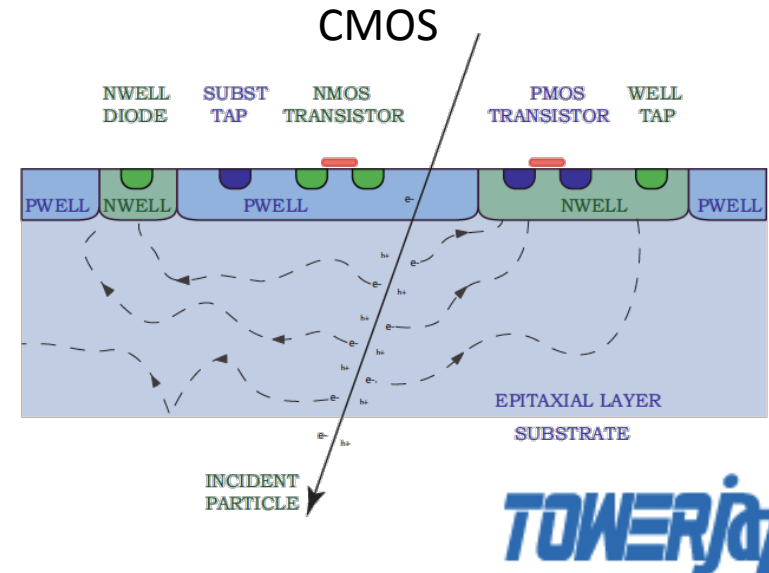
Inner barrel prototype

Pixel chip technology R&D

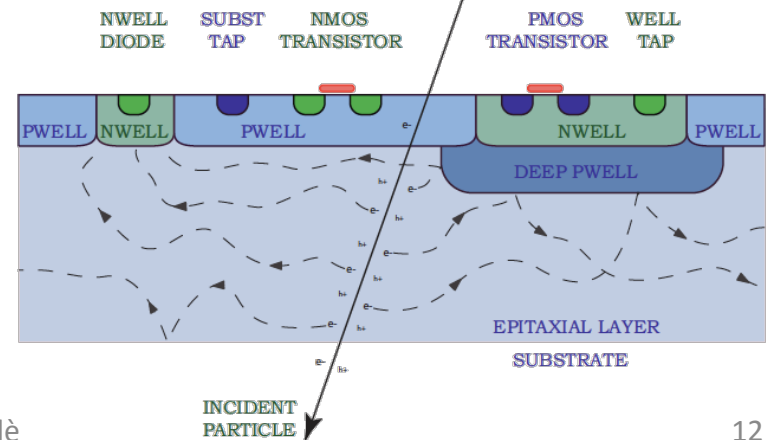
New specialty CMOS technologies available for monolithic pixel detectors.

Development of monolithic detectors using

- Tower/Jazz 0.18 μm CMOS technology:
 - Improved TID resistance due to smaller technology node
 - Available with high resistivity (1-5k $\Omega\cdot\text{cm}$) epitaxial layer up to 40 μm (substantial depletion at 1-2V)
 - Special quadruple-well available to shield PMOS transistors (allows in-pixel truly CMOS circuitry)



CMOS with deep p-well

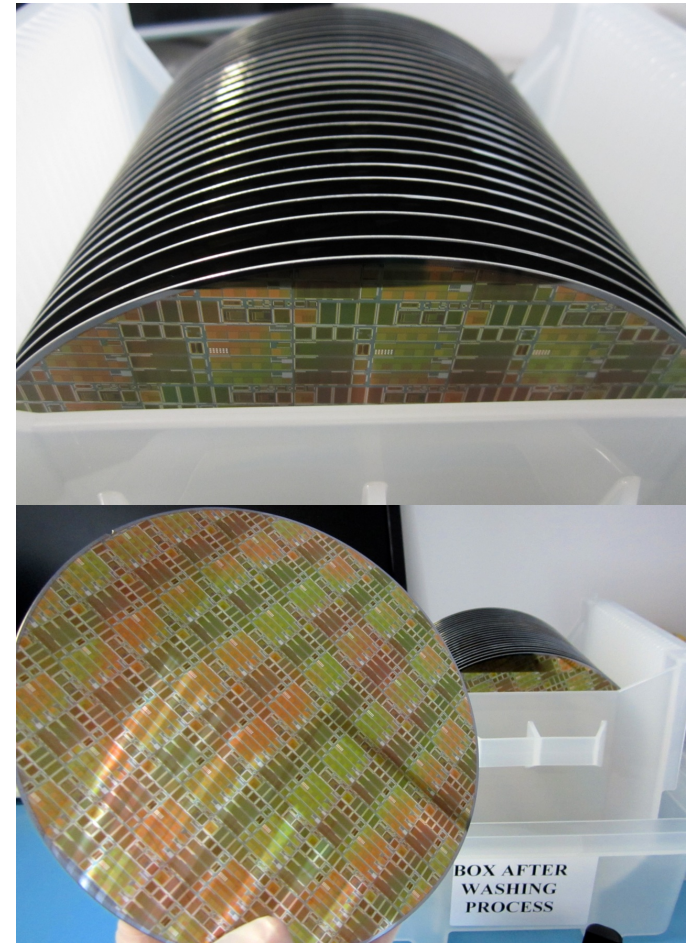


Pixel chip architecture

- MIMOSA (IPHC Strasbourg) – baseline (most mature and advanced)
 - Rolling shutter with in-pixel CDS, column-level discriminator, 2 rows parallel RO
 - Integration time: 30 μ s
 - Power ≤ 400 mW/cm² (ANALOG+DIGITAL)
- CHERWELL: Parallel Rolling Shutter (RAL)
 - Based on previous development.
 - Integration time: ~ 40 μ s
 - Power < 200 mW/cm²
- EXPLORER: In-pixel discriminator + data driven readout (CERN)
 - shaping time ~ 2 μ s, readout time ~ 4 μ s; $<$
 - Power ~ 100 mW / cm² (ANALOG ONLY)
- SENSOR OPTIONS
 - collection electrode geometry
 - pixel dimensions/shape etc...
- READ-OUT OPTIONS
 - Priority encoder
 - Orthopix
 - Parallel rolling shutter
 -

Engineering run march 2013

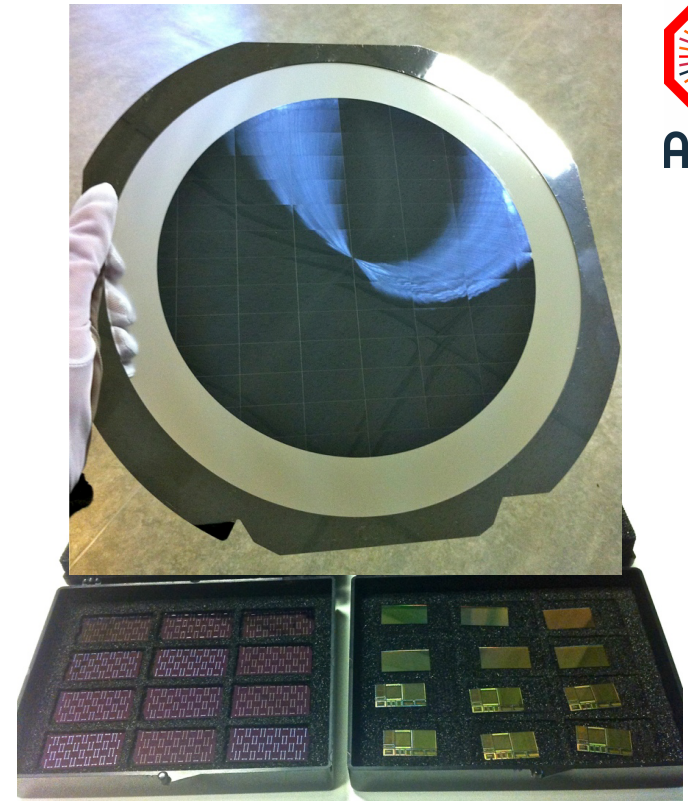
- High resistivity wafers procurement
 - Nominal resistivity (30; >1k; >2k Ωcm)
 - Different epitaxial layer thickness (12-40 μm)
- Complex dicing scheme, 26 dices per reticle:
 - Pixel matrices with:
 - Different architectures (IPHC-CERN-RAL)
 - Different anode shapes and dimensions
 - Different read-out options
 - Resistivity measurements test structures
 - Data transmission logic blocks
- Wafers delivered June 12th
 - Sent to company for thinning and dicing
 - Ready for tests



Thinning @ 50 μm and dicing

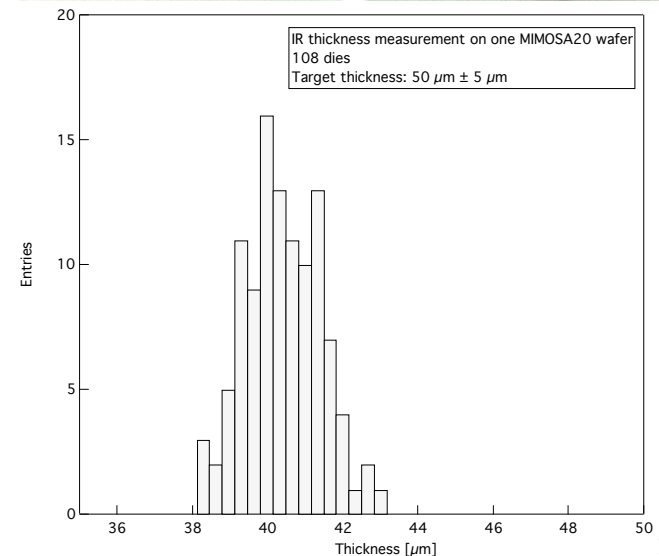
Work with commercial supplier to thin wafers to 50 μm assuming chip size of 15 mm x 30 mm

- Thinning and dicing of blank 200 mm wafers (13) – 2012
- Thinning and dicing of patterned 200 mm wafers (pads for interconnection tests) – 5 wafers – 2012
- Thinning and dicing of one MIMOSA20 wafer (die size 10 mm x 20 mm) – completed



Metrology tests confirm thickness within expectations: 50 \pm 5 μm

- IR measurement does not take into account metal and inter-metal layers; there are 6 metal-layers corresponding to \sim 10 μm offset

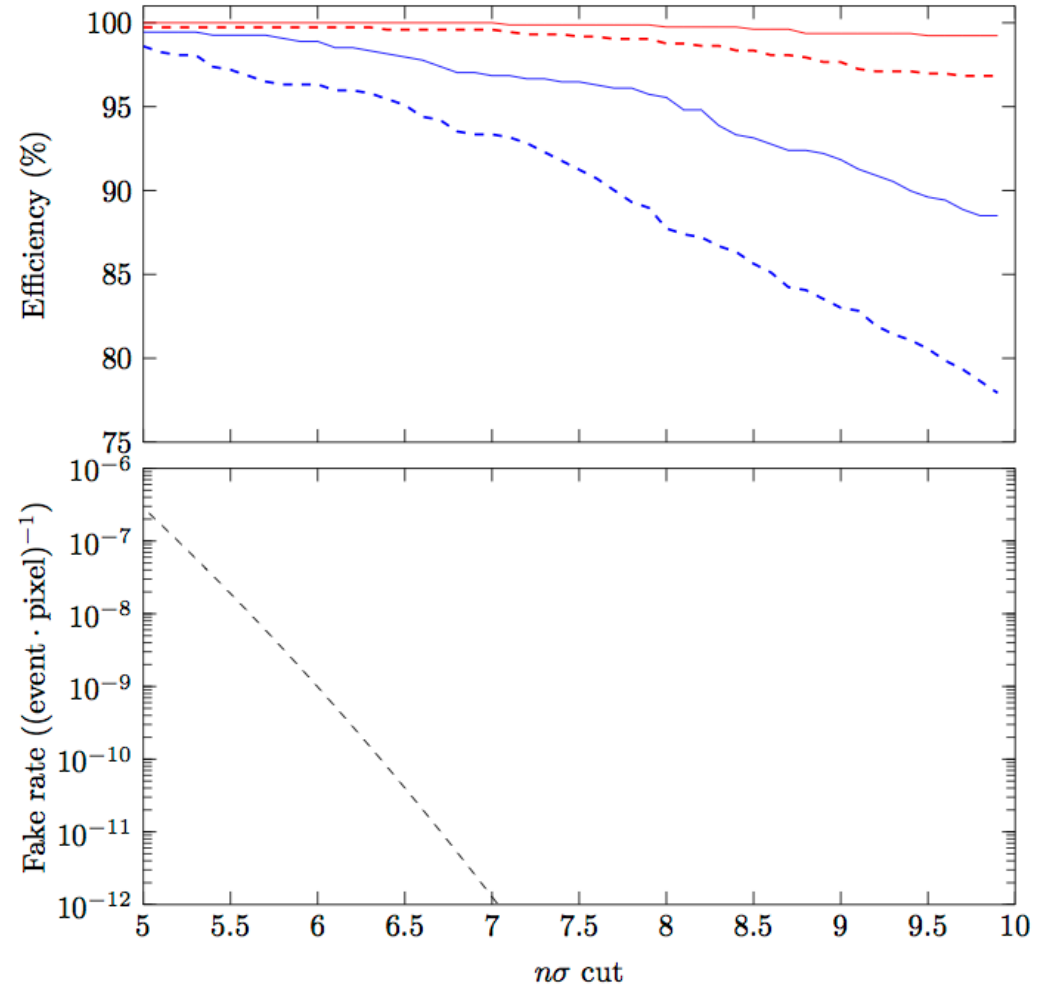
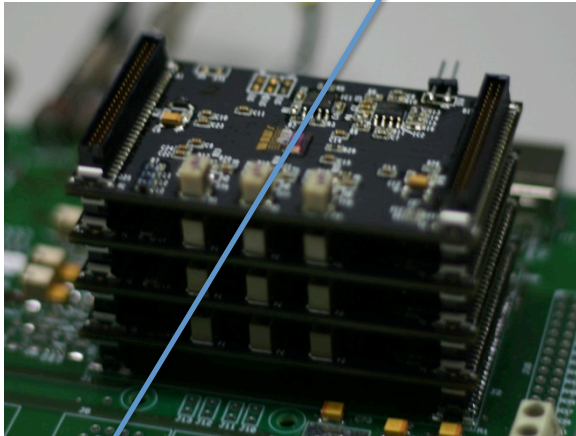


Test beams (1)



--- $30 \times 30 \mu\text{m}^2$, $V_{\text{bias}} = -1 \text{ V}$ — $20 \times 20 \mu\text{m}^2$, $V_{\text{bias}} = -1 \text{ V}$
--- $30 \times 30 \mu\text{m}^2$, $V_{\text{bias}} = -6 \text{ V}$ — $20 \times 20 \mu\text{m}^2$, $V_{\text{bias}} = -6 \text{ V}$

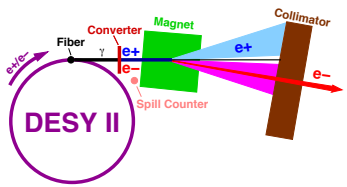
- Test Beams:
 - CERN PS - December 2012
 - Explorer chip: 4 chips forming a self-contained telescope at PS



High efficiency (>99%) at low fake hit rates

Reverse substrate bias gives extra margin

Test beams (2)

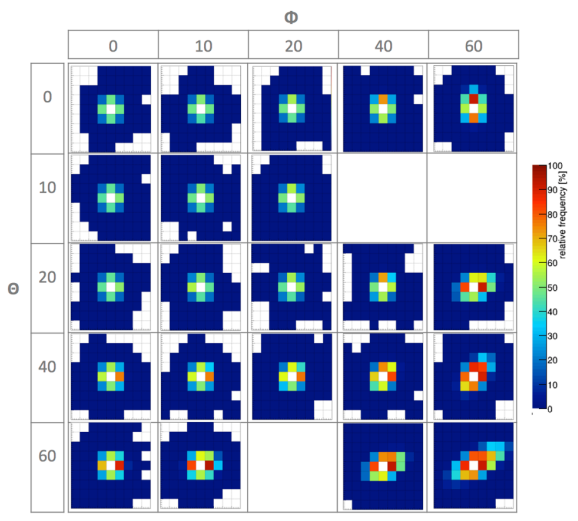
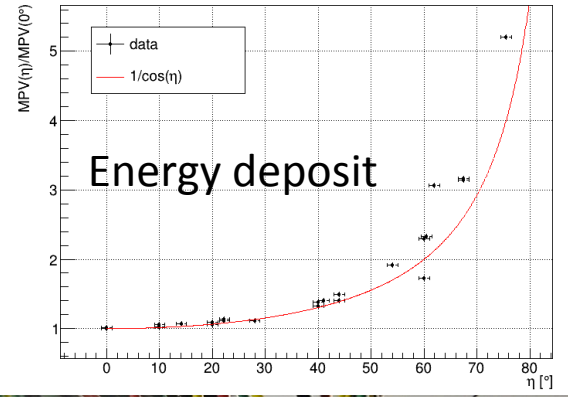
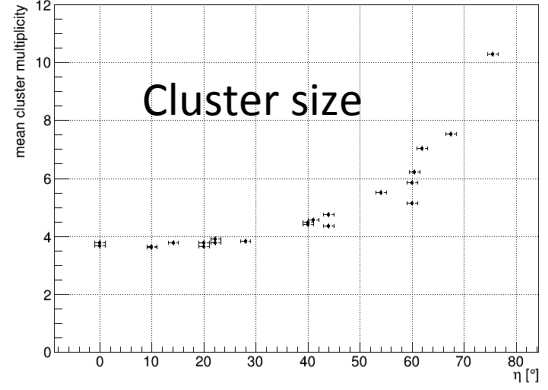


- Test Beams:
 - DESY - March 2013
 - DESY - June 2013
 - DESY – July 2013

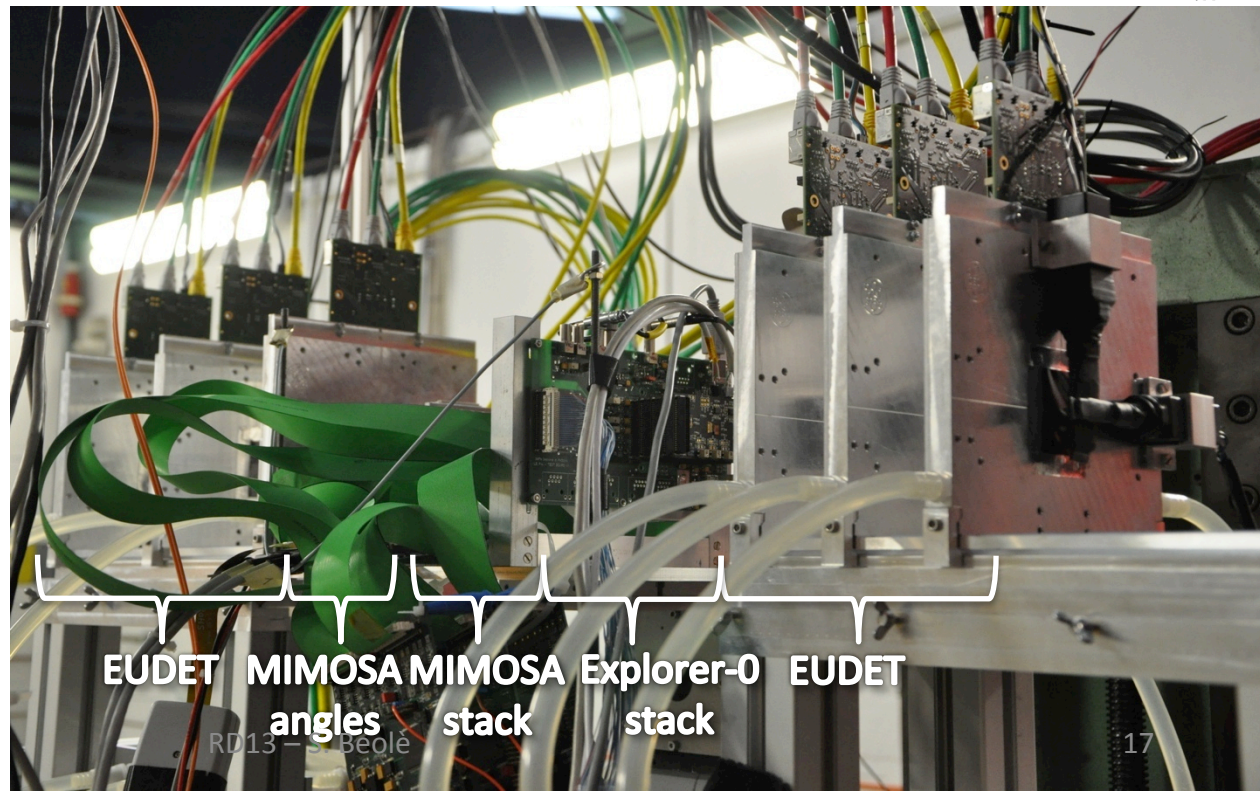
Goals:

- Verification of MC model for inclined tracks
- Characterization of irradiated samples

MIMOSA 32



July 4, 2013



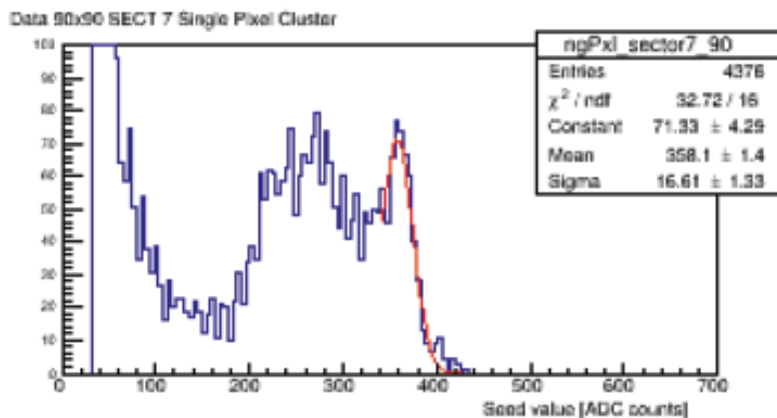
Preliminary results on Explorer-0

Charge collection efficiency measured with Fe^{55} source

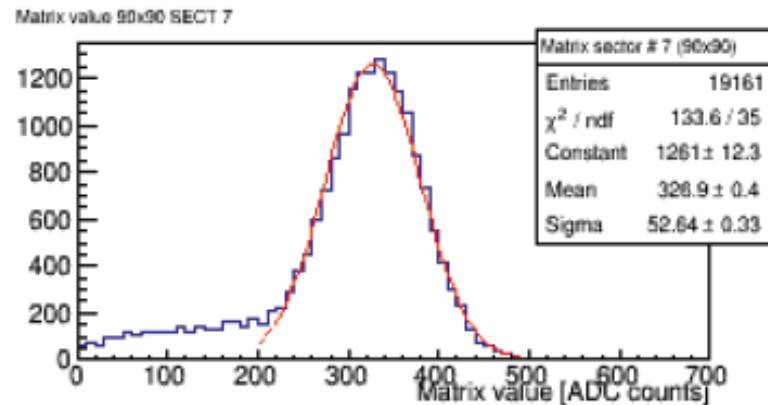
- CCE is calculated as the ratio between the MPV of the charge collected in a cluster divided by the single pixel collection peak value
- CCE measured for
 - different pixel size
 - different V_{bias} values (-1; -6 V)
 - with and without threshold on the seed surrounding pixels

Very good (>98%) charge collection (-> detection) efficiency for pixel size $\sim 20\mu\text{m} \times 20\mu\text{m}$

A) Seed spectrum
(single-pixel clusters)



B) Cluster spectrum
(sum of 5×5 -matrix around peak)



Radiation Damage tests

Chip	Period	Facility	Radiation type	Results
TJ180_TID	August 2012/ February 2013	CERN	10 KeV X-Ray (TID < 10 Mrad)	Study of the CMOS Threshold shift and leakage current => adequate tolerance for ALICE ITS
TJ180_SEU	April 2013/ May 2013	NPI Prague	Proton beam (28 MeV, 35 MeV)	SEU Cross section (per bit): 10^{-13} cm^2 (Very preliminary results) => adequate tolerance for ALICE ITS
Explorer0	December 2012	CERN	PS, Line T10	No radiation damage studies. Tracking efficiency with 5 GeV/c pions: ~ 100% tracking efficiency at 5σ threshold.
Explorer0	March 2013	DESY	Electron beam	(First result on non ionizing radiation damage $10^{13} n_{eq}$) Evaluation of the Noise (+8%) and Signal to Noise (-13%)
Explorer0	17 June 2013 -> 25 June 2013	DESY		
Explorer0	22 July 2013 -> 04 August 2013	DESY		

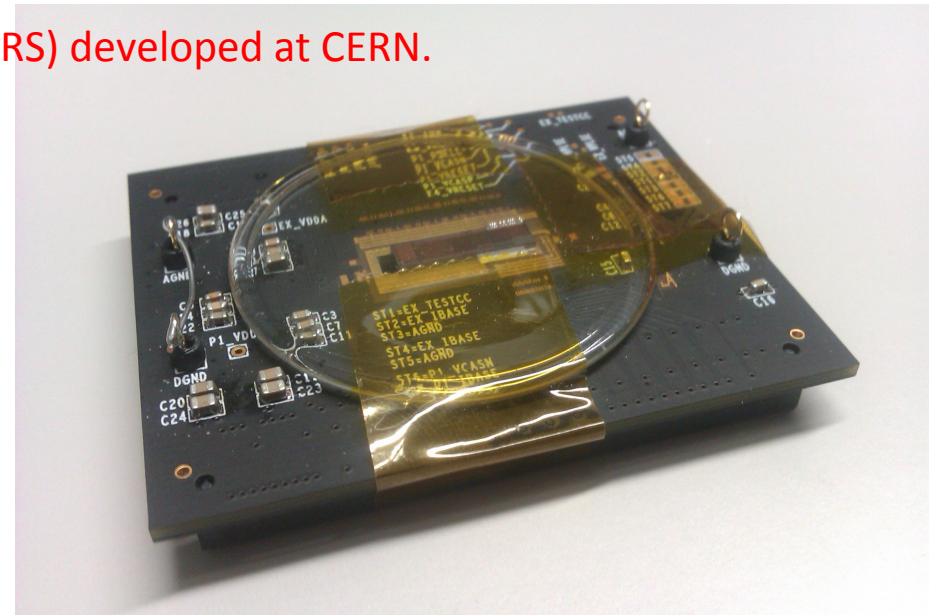
Very preliminary results on Explorer-0 and test structures

Beam test data analysis ongoing



Architecture qualification

- Dedicated test system developed in the framework of the chip design
 - Hybrid board to allocate DUT, custom for each chip.
 - Developed by UK (Cherwell) and CERN (Explorer-1 & Priority encoder)
 - Ready to bond first dices from engineering run
 - Proximity board, common to all chips.
 - Designed by Padua, production and assembly to be done at CERN. First version equipped with components
 - Under test NOW
 - DAQ system, common to all chips.
 - Use of “Scalable read-out system” (SRS) developed at CERN.
- Test campaign
 - Fe55
 - Laser tests
 - Beam tests @ Desy (July-August)

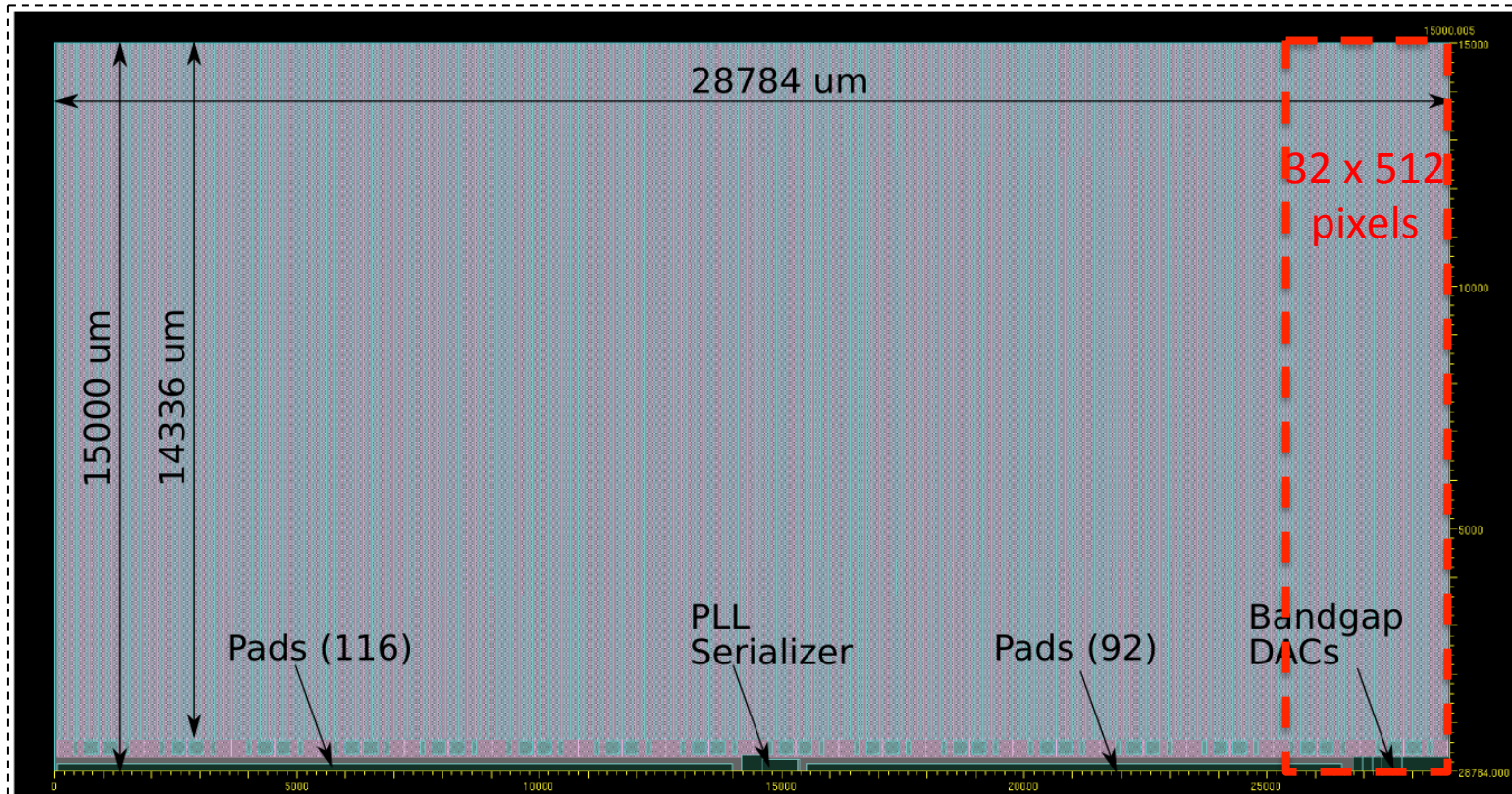


first results expected within the end of July

Engineering run end of 2013: large scale demonstrator

- Based on the priority encoder & front end circuit already submitted in the previous engineering run
 - 32 regions of 32 columns each, 512 pixels per column ($28\ \mu\text{m} \times 28\ \mu\text{m}$) $\approx 29\ \text{mm} \times 15\ \text{mm}$

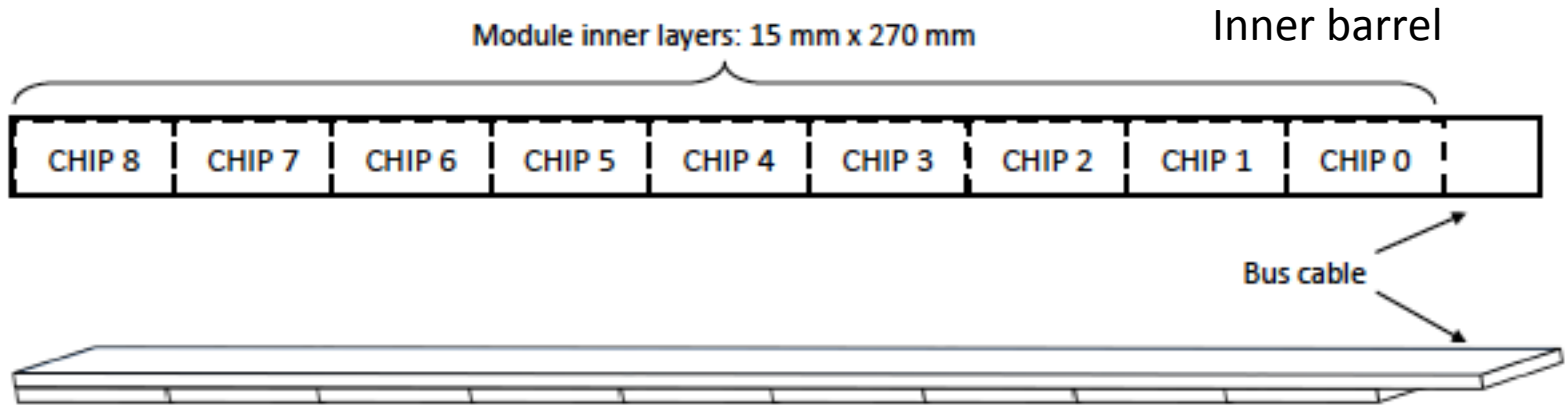
Pixel sub-matrix: 0 \rightarrow 31



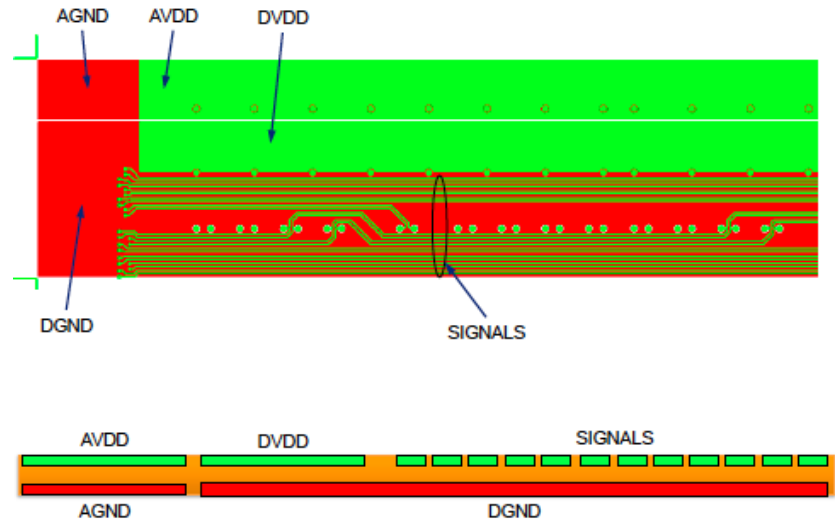
System aspects

- Very large chip: optimization of architectural aspects in pixel matrix and digital circuitry/data transmission
 - constraints on digital circuitry due to timing/area
 - power consumption (0.3-0.5 W/cm² power budget is upper limit)
 - Operation with realistic trigger rate and detector occupancy: data compression, multi-event buffer
 - Serializer
 - Effects of the connection pads
- Production Yield
- Chips used to produce working modules for inner and outer barrel

Flex Printed Circuit



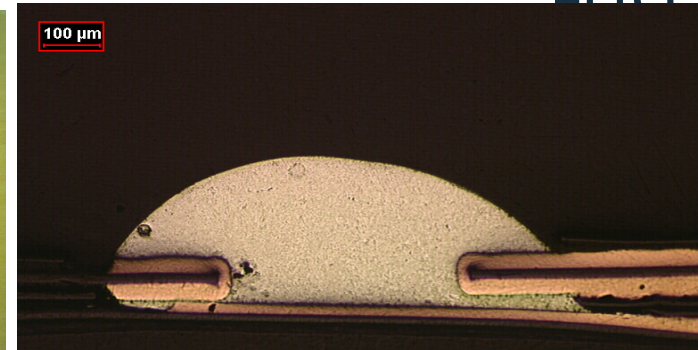
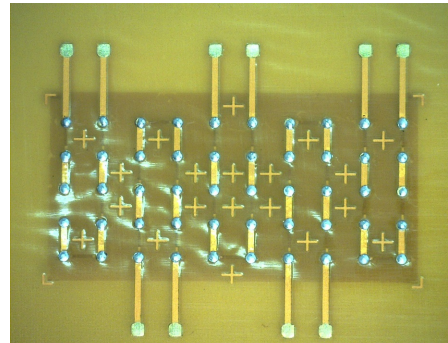
- Bus cable:
 - Al + polyimide + Al
- Chip-On-Flex connections:
 - Au-stud
 - Laser soldering



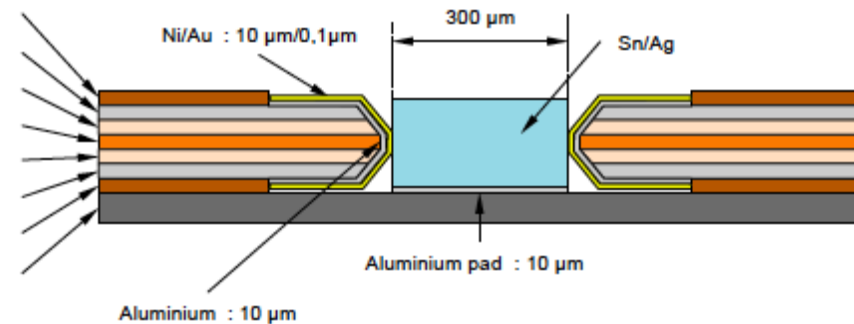
Soldering techniques

Laser soldering:

- First validation of the technique by soldering kapton-kapton assemblies
- Solder 50 μm silicon die to polyimide foil representing the module PCB
- Tests ongoing with different solder ball sizes



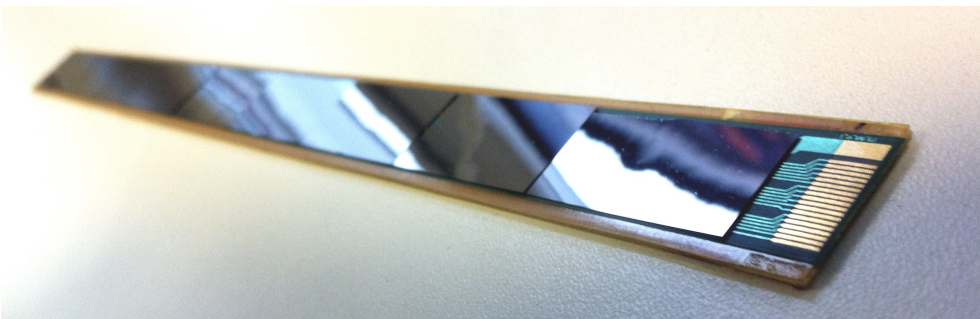
- Coverlay : 25 μm
- Aluminium : 25 μm
- Glue : 25 μm
- Polyimide : 25 μm
- Glue : 25 μm
- Aluminium : 25 μm
- Coverlay : 25 μm
- Silicium chip : 50 μm



Au-stud:

First dummy module produced using silicon chips (50 μm) and a polyimide PCB (27 cm long, 9 chips)

- Au stud bonding using 80 μm diameter stud on chip (100 contacts per chip, 400 μm diameter pads)
- Bus connected using conductive glue drop (glue polymerized at 80°C)
- Further optimization of the bus layout and study of the polymerization temperature needed



Timeline

- 2012–2014 R&D
 - 2012 evaluation of technologies & prototypes
 - 2013 selection of technologies, eng. Design, TDR
 - 2014 final design and validation
- 2015-18 Construction and Installation
 - 2015-16 production, construction and test of detector modules
 - 2017 assembly and pre-commissioning
 - 2018 installation in the cavern

Summary

The ALICE Inner Tracking System Upgrade will allow to address new physics topics like:

- Quark mass dependence of in-medium energy loss
- Thermalization of heavy quarks in the medium
- Heavy nuclear states production

New Tracker composed of 7 silicon layers characterized by:

- Impact parameter resolution improved by factor 3x
- First detecting layer @22 mm from the beam line
- Material budget $x/X_0 \sim 0.3\%$ in the first layers
- High tracking efficiency down to low p_T ($> 95\%$ for $p_T > 200$ MeV/c)
- Fast access for maintenance

Detector technology evaluation ongoing - to be installed during LS2